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A Virtual Reactor for Simulation of Plasma Enhanced Chemical Vapor Deposition

ACADEMISCH PROEFSCHRIFT

ter verkrijging van de graad van doctor
aan de Universiteit van Amsterdam
op gezag van de Rector Magnificus
prof. dr. D.C. van den Boom
ten overstaan van een door het college voor promoties ingestelde
commissie, in het openbaar te verdedigen in de Agnietenkapel
op Vrijdag 20 Juni 2008, te 12:00 uur

door

Valeria Vladimirovna Krzhizhanovskaya

geboren te St. Petersburg, Rusland
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To my family…